

NS-FH-532/1-30W

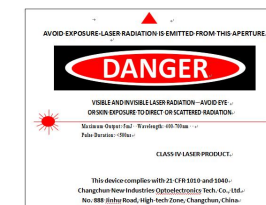
NANOSECOND PULSED LASER AT 532nm

Nanosecond pulsed laser at 532nm is made features of short pulse duration, high repetition rate, high stability and good beam quality, which is used in sapphire marking, ceramic cutting, semiconductor cutting, film scribing, physics experiment, etc.

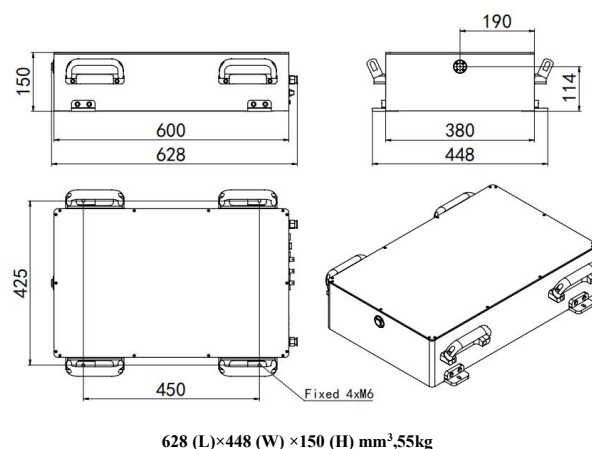


SPECIFICATIONS

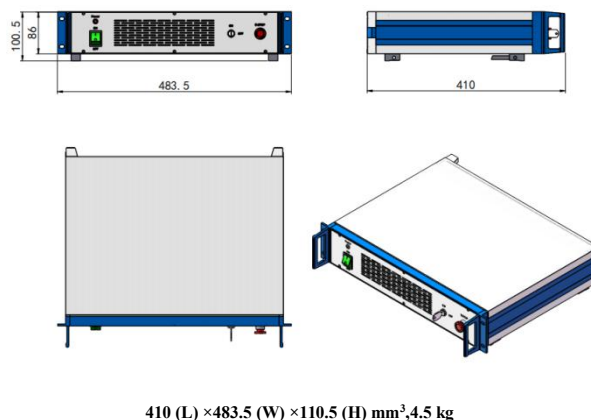
Wavelength (nm)	532±1
Operating mode	Pulsed
Average power (W) ¹	1-30
Single pulse energy (uJ)	100μJ@200kHz; 30μJ@1MHz; 20μJ@1.5MHz
Rep. rate ²	0.2-10MHz
Pulse duration (ns) ³	2-10@1.5MHz
Peak power (MW)	1-20
Ave power stability (rms, 4 hours±3°C)	<2%, <1%
Warm-up time (minutes)	<10
Transverse mode	TEM ₀₀
M ²	<1.3
Beam divergence, full angle (mrad)	<1
Beam diameter at the aperture (1/e ² ,mm)	<3
Polarization ratio	>100:1 Horizontal
Beam height from base plate (mm)	114
Cooled method	Water cooled
Operating temperature (°C)	10-35
Power supply (100-240VAC)	RAD1PS
Expected lifetime (hours)	>10000



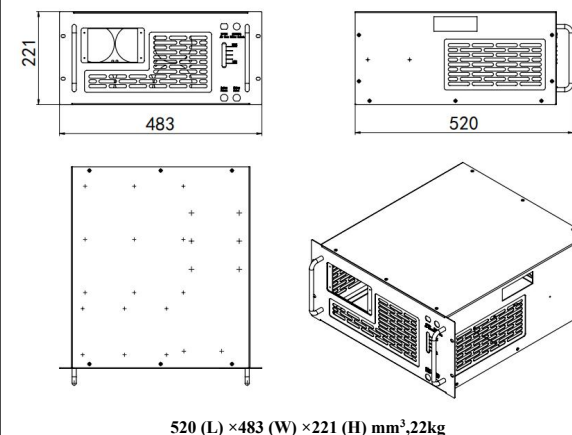
LASER HEAD (DRIVER Integrated)



POWER SUPPLY



WATER CHILLER



1 One fixed value between 1-30W.

2 Rep.rate range available on request.

3 Pulse width range available on request.